



The Nanotechnology Solutions Partner

www.parkAFM.com

Workshop on Atomic Force Microscope and Nanotechnology
(Attendance is free with RSVP)

Park Systems is pleased to invite you to a workshop on AFM applications
in nanotechnology
and demonstration of the award-winning XE-70 AFM.
The agenda for each workshop includes:

- 10:00 – 10:15 Introduction
- 10:15 – 11:00 "Overview of the XE-series AFM/SPM R&D instrumentation"
- 11:00 – 11:45 "Advanced applications utilizing the ancillary modes of the XE-series AFM/SPM R&D instrumentation"
- 11:45 – 12:45 Complimentary Lunch
- 12:45 – 14:30 Demonstration

Workshops will be held at the following locations:

Wednesday, September 24, 2008

Cerium Labs. (all visitors welcome)
5204 E. Ben White Blvd., Bldg 1, Austin, TX 78741
10am – 2:30pm

Thursday, September 25, 2008

Nanotechnology Center, Univ. of Texas, Bldg NST
102 E. 24th St., Austin, TX 78712
Room 1.104
10am – 2:30pm

Friday, September 26, 2008

Location TBD depending on demand
Dallas or Houston
10am – 2:30pm

Please RSVP to Park Systems at 408-986-1110 or at sathya@parkafm.com. Be sure to bring samples (to be imaged later at our Application Labs.).

Park Systems is the nanotechnology solutions partner for the most demanding imaging and measurement needs in research and industry. The company serves the customers with optimized metrology solutions in nanoscale including atomic force metrology tools, software, and global service and support.

25-Year History in AFMs



The root of Park Systems can be found at Stanford University, the birthplace of atomic force microscope; Drs. Sang-il Park (Chairman and CEO) and Sung Park (General Manager of US Operations), original founders of Park Scientific Instruments, were applied physics graduates at the University and developed the world-fist commercial AFM in 1989. The spin-off company (PSIA) was renamed Park Systems in 2007. Following continuous growth over 20 years, Park Systems currently has over 400 customers across the world in industry and research.

Evolution of Commercial AFM Technology Driven by Park Systems



Advantages of XE Technology



The award-winning XE-platform, completely eliminates background scanner curvature and shows no bowing even on scans of the flattest samples, thus enabling precision nanometrology for even the most challenging problems in industry and research.

Park Systems Clients

Park Systems' unique strength to deliver customized solutions by forming successful partnership with clients have been acknowledged by world leaders in industry including Seagate, Hitach, LG and Samsung. Our research products line has well-established reputation among world-class universities and research institutes including Harvard, Stanford and NASA.

Park Systems Worldwide



The Company has three overseas offices in the U.S., Japan, and Singapore and currently, **Park Systems** has developed global sales network over 21 countries.

Park Systems Product Line



XE-3DM
For Undercut and Sidewall Metrology



XE-CMP
For High Aspect Ratio Trench and CMP Metrology



XE-HDM
For General Hard Disk Media
and Substrate Inspection and Metrology



XE-LCD
For Automated LCD Production
Inspection and Metrology



XE-PTR
For In-line Pole Tip Recession Metrology
of Hard Disk Sliders



XE-WAFER
For Wafer-based Inspection and Metrology



XE-70
Affordable, Research-Grade AFM
with Flexible Sample Handling



XE-100
Versatile, Research-Grade AFM
with Motorized Optics



XE-150
Premier Cross-Functional AFM
with Motorized Sample Stage



XE-200
Enlarged Capacity Cross-Functional AFM
with Motorized Sample Stage



XE-Bio
Bio Research in Nanoscale: In-liquid
imaging and much more



XE-NSOM
For NSOM or Raman-AFM measurements